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(12) **United States Design Patent**
Ota et al.

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(45) **Date of Patent:** **** Jun. 24, 2008**

(54) **TOP PANEL FOR MICROWAVE
INTRODUCTION WINDOW OF A PLASMA
PROCESSING APPARATUS**

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Tian**, Amagasaki (JP); **Junichi
Kitagawa**, Amagasaki (JP)

(Continued)

(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

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(**) Term: **14 Years**

EP 0592017 A2 * 4/1994

(21) Appl. No.: **29/252,833**

(22) Filed: **Jan. 30, 2006**

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(30) **Foreign Application Priority Data**

Jul. 29, 2005 (JP) 2005-022108

Asian Sources Hardwares for World Markets, High Quality Ductile and Grey Iron OEM Products From One of Taiwan's Leading Manufacturers, Nov. 1990, 1 cover Page and p. 251.

Primary Examiner—Sandra Snapp
Assistant Examiner—Patricia Palasik

(51) **LOC (8) Cl.** **15-09**

(52) **U.S. Cl.** **D15/138; D15/199**

(58) **Field of Classification Search** D7/586,
D7/587, 501, 553.6, 600.4; D8/70, 74; D9/445,
D9/454, 456; D15/133, 144.1, 199, 122,
D15/138, 139; 117/103; 118/723 AN, 723 ME,
118/723 MP, 723 MW, 723 E, 723 ER; 216/69,
216/67; 257/E21.252, 252, 629, 631, E39.001;
427/562, 571, 575; D1/126, 128; D6/455;
D13/122, 138, 139, 158-177, 182; D18/17;
156/242, 345; 175/374, 434; 204/298.38;
219/420-424, 523, 530, 541, 544; 264/328.14,
264/328.15, 328.16; 313/231.31; 315/111.21;
407/113-118; 408/145; 425/547-550, 564,
425/566, 570; 451/540-548; 700/121, 123

See application file for complete search history.

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Maier & Neustadt, P.C.

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(57) **CLAIM**

The ornamental design for a top panel for microwave introduction window of a plasma processing apparatus, as show and described.

DESCRIPTION

FIG. 1 is a front view of a top panel for microwave introduction window of plasma processing apparatus showing our new design;

FIG. 2 is a rear view thereof;

FIG. 3 is a right side view thereof;

FIG. 4 is a left side view thereof;

FIG. 5 is a top plan view thereof;

FIG. 6 is a bottom plan view thereof;

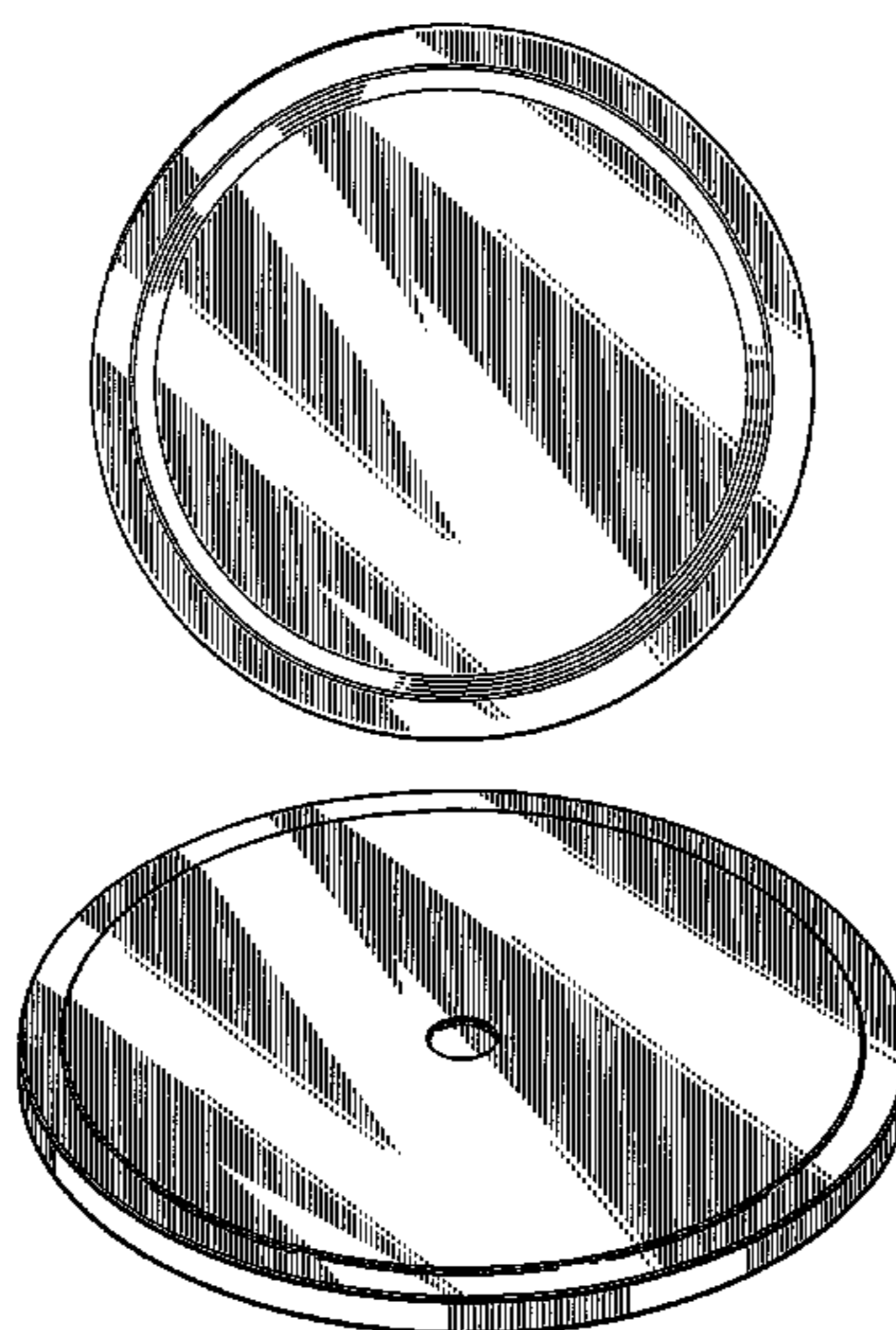
FIG. 7 is a sectional view taken along line 7—7 of FIG. 5;

FIG. 8 is an enlarged view taken along line 8—8 of FIG. 7;

FIG. 9 is an enlarged view taken along line 9—9 of FIG. 7; and,

FIG. 10 is a perspective view thereof.

1 Claim, 4 Drawing Sheets



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FIG. 1

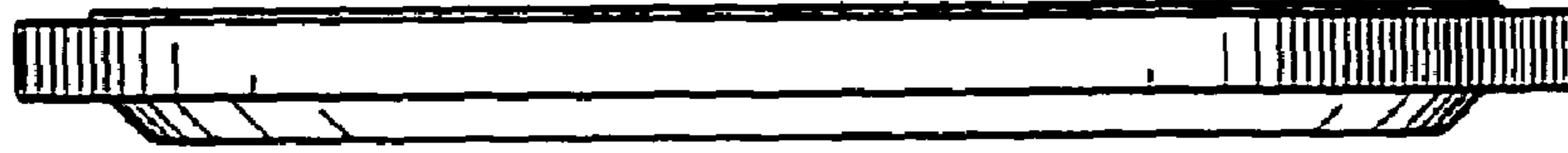


FIG. 2

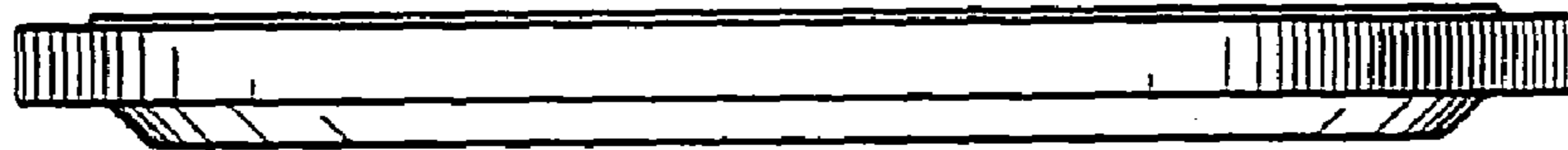


FIG. 3

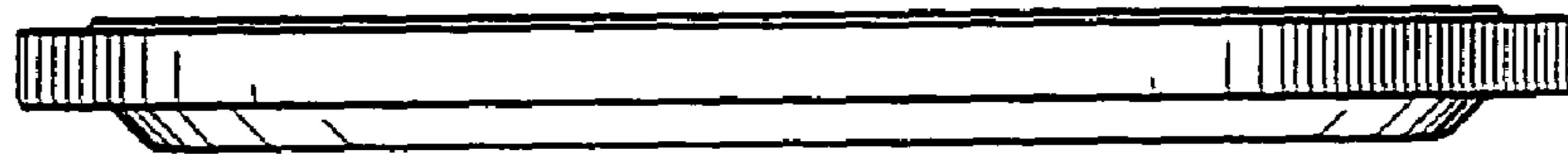


FIG. 4

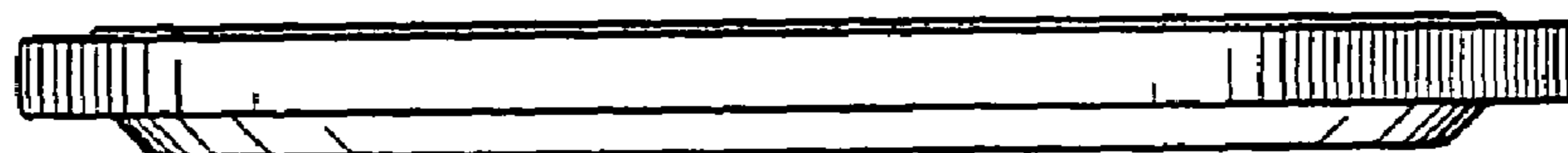


FIG.5

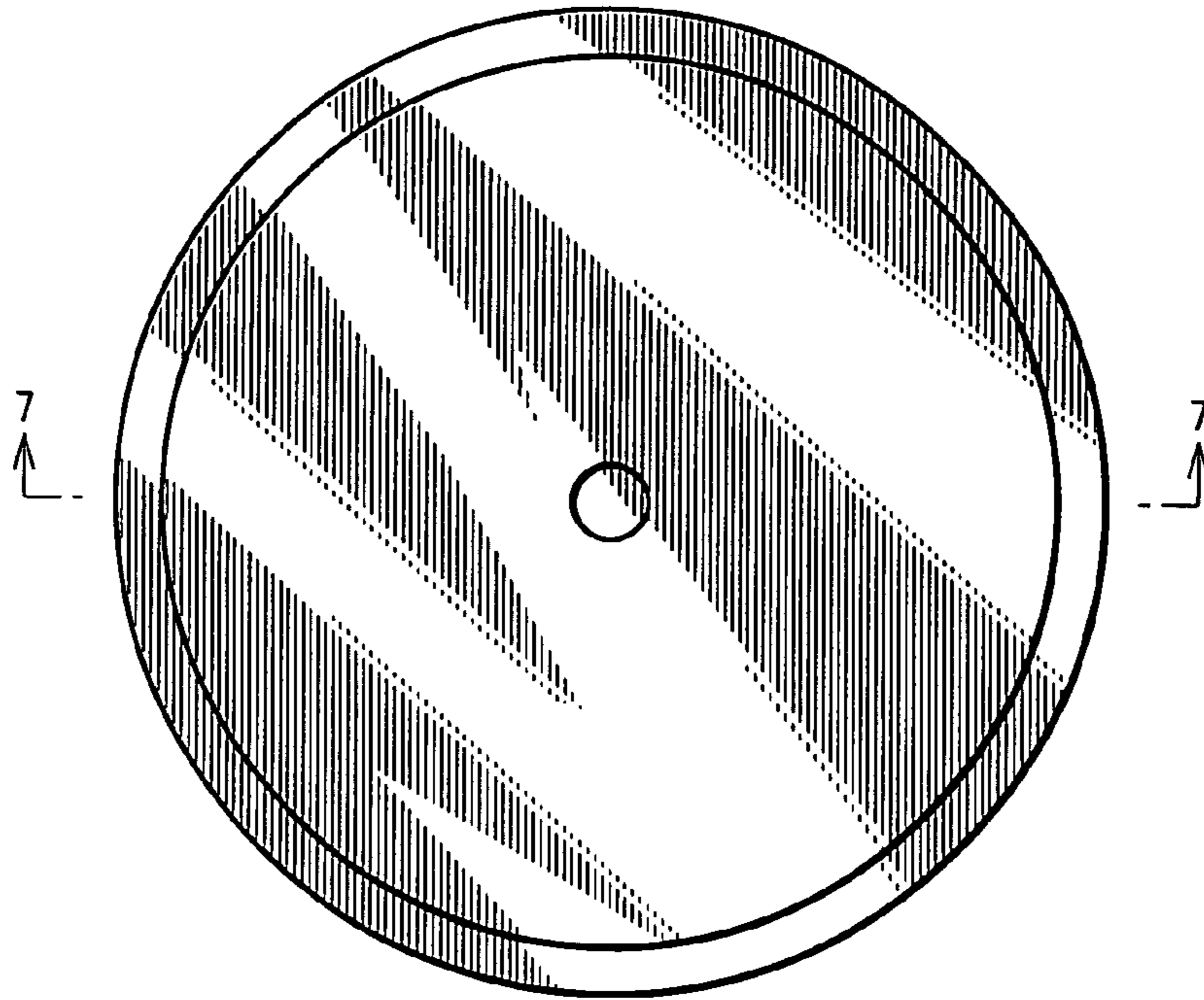


FIG.6

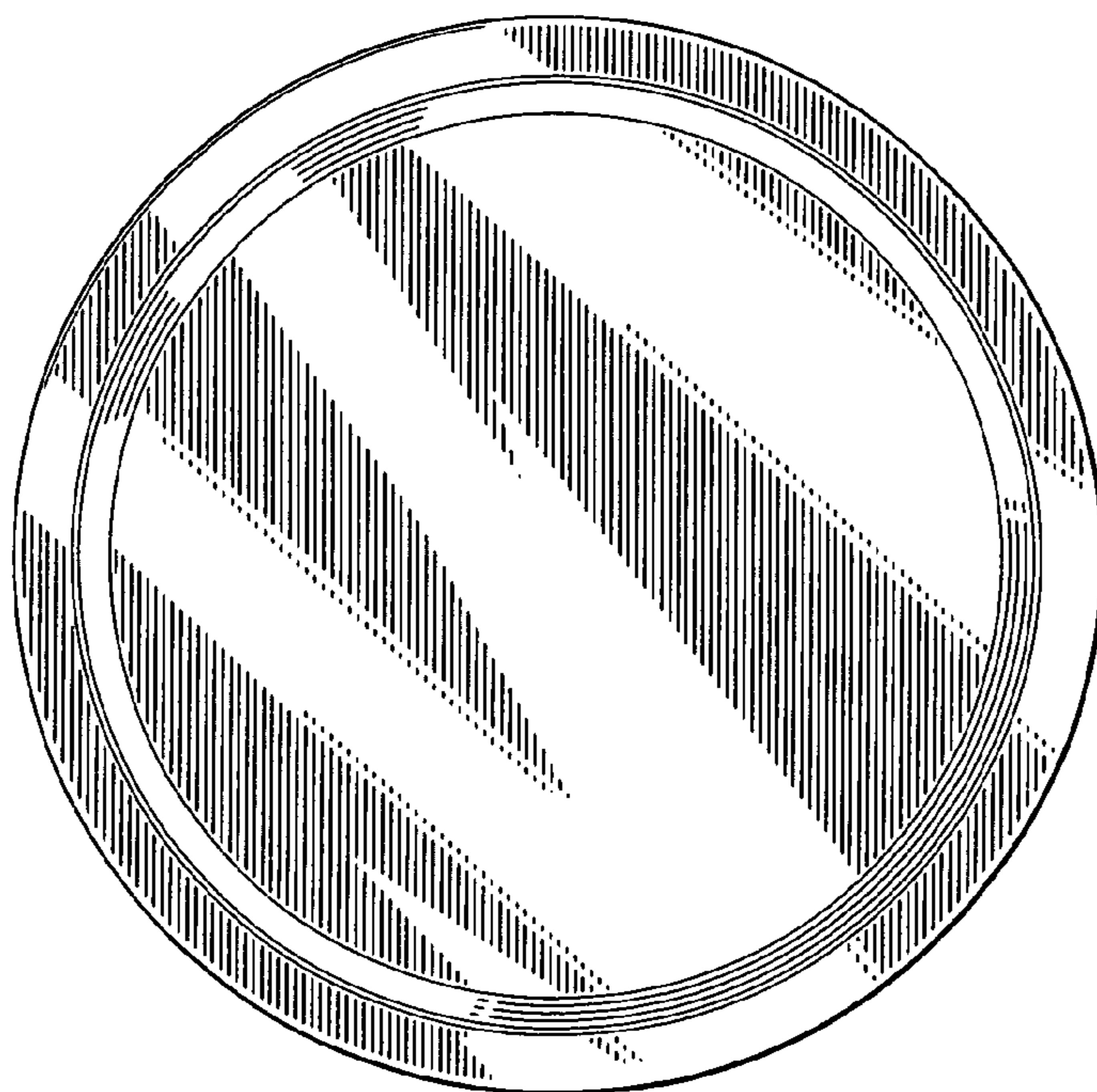


FIG.7

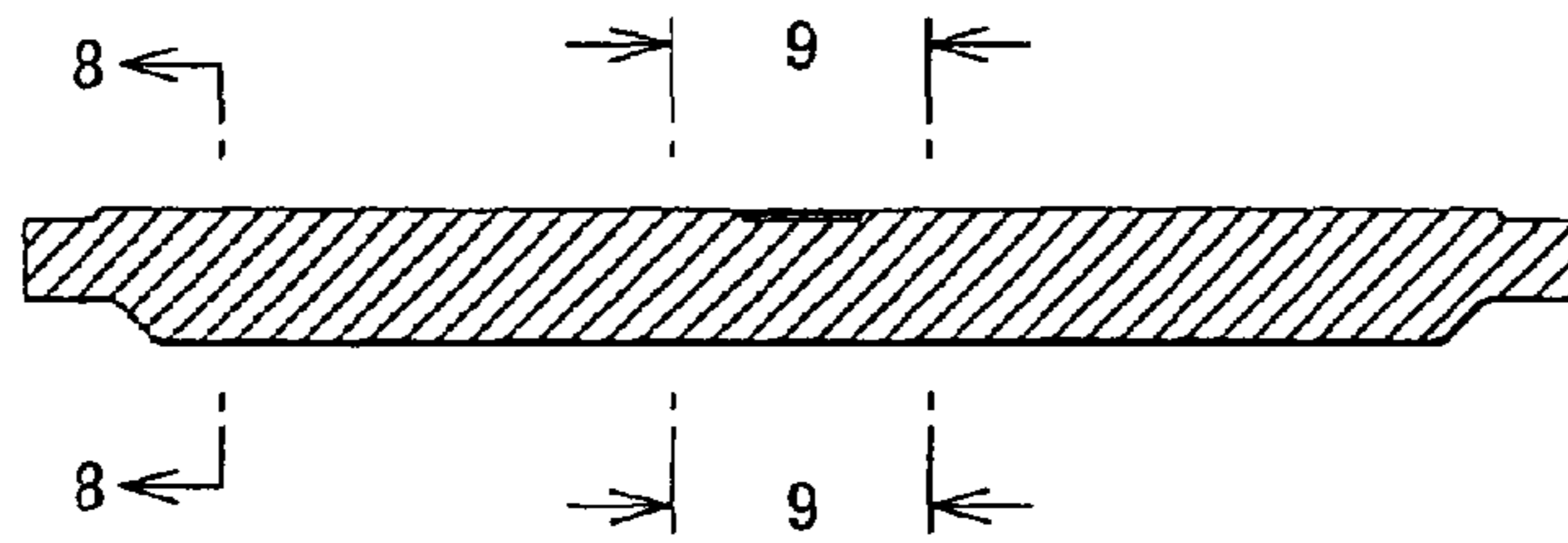


FIG.8

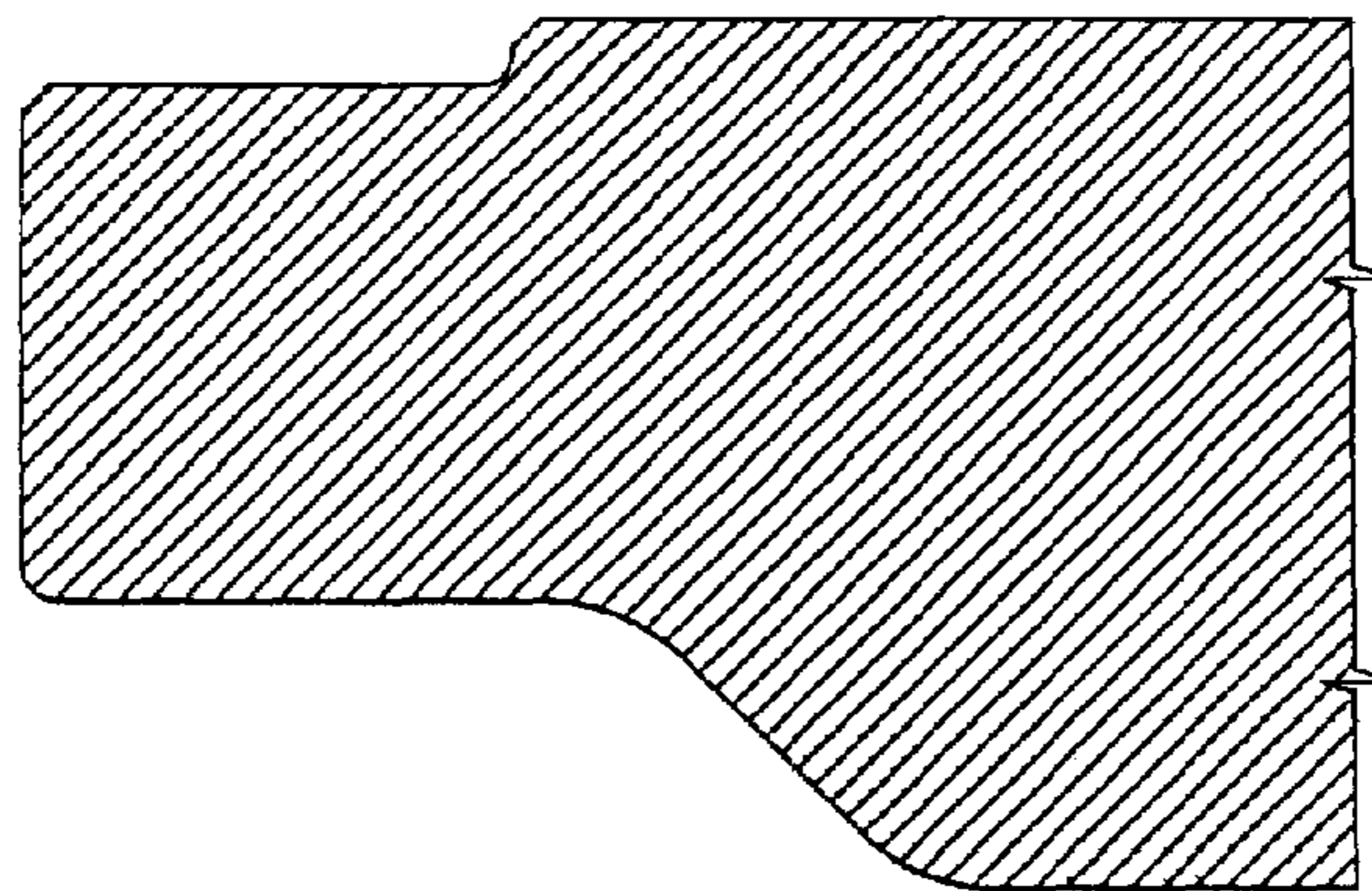


FIG.9

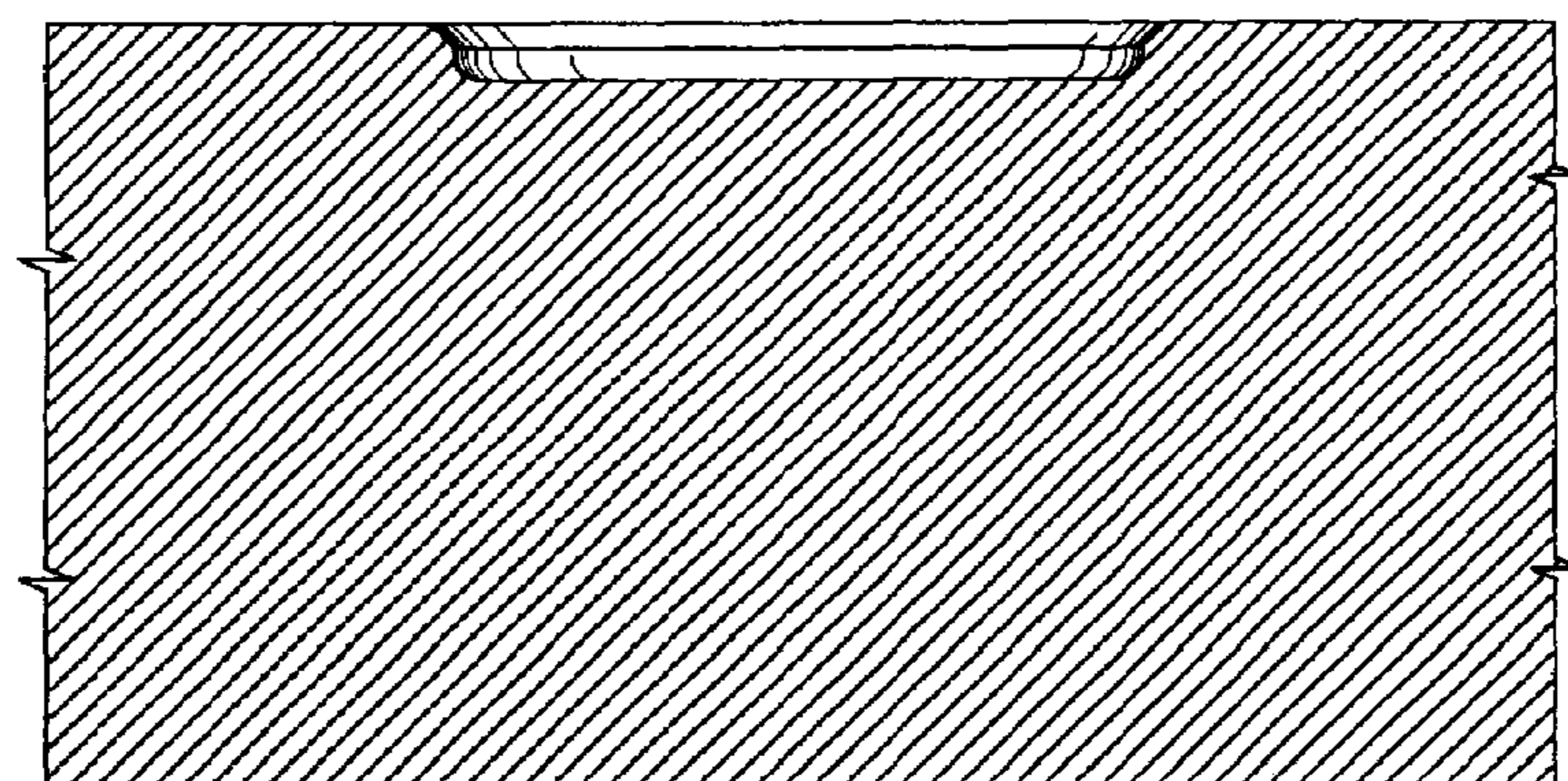


FIG. 10

